



Industrial Instruments General Brochure

The highly cost-effective SMZ series offer outstanding optical performance, flexible system expandability, and superb operability.

Parallel Optics Type								
	SMZ25	SMZ18	SMZ1270 SMZ1270i	SMZ800N				
Zoom Ratio	25 : 1	18 : 1	12.7 : 1	8:1				
Zoom Range	0.63-15.75×	0.75-13.5×	0.63-8×	1–8×				
Total Magnification*1 (Standard combination*2)	3.15-945× (6.3-157.5×)	3.75-810× (7.5-135×)	3.15-480× (6.3-80×)	5–480× (10–80×)				
WD *3	60 mm	60 mm	70 mm	78 mm				
Camera	V	V	✓	<u> </u>				

Greenough Type								
	SMZ745			2445		SMZ-2		
7 D. kin	SMZ745T	H		2460	H			
Zoom Ratio	7.5 : 1		4.4 : 1	4.3 : 1		5:1		
Zoom Range	0.67–5×		0.8 –3.5×	0.7 –3×		0.8–4×		
Total Magnification* ¹ (Standard combination* ²)	3.35-300× (6.7-50×)			3.5–60× (7–30×)		4–120× (8–40×)		
WD *3	115 mm		100	mm		77.5 mm		
Camera	✓ (SMZ745T only)		_	_		_		
						✓ : Available / — : Not available		

*1: Depending on combination of Eyepiece and Objective lens.	*2: Combination of Eyepiece 10× and Objective lens 10×.	*3: Objective lens 1× or no Auxiliary lens.

INDEX	
Stereo Microscopes	3
Parallel Optics Type - SMZ25 / SMZ18 / SMZ1270 / SMZ1270i / SMZ800N Greenough Type - SMZ745 / SMZ745T / SMZ445 / SMZ460 / SMZ-2	
Industrial Microscopes 4-	-5
Upright Microscopes - LV100ND LED / LV100NDA LED / LV150N / LV150NA / L200N / L200ND / L300ND Inverted Metallurgical Microscopes - MA100N / MA200 Polarizing Microscopes - LV100NPOL LED / Ci POL	
Digital Cameras for Microscopes 6-	-7
Microscope Camera- Digital Sight 1000Microscope Camera- Digital Sight 100Microscope Camera- Digital Sight 10Imaging Software- NIS-Elements LE, D, Ar, BR	
Objective Lenses	8
Objective Lenses – CFI60-2 / CFI60	
For Incorporation into Microscopes / Wafer Loaders	9
Modular Focusing Units - IM-4 / LV-IM / LV-FM Wafer Loaders - NWL200 Series Compact Reflected Microscopes - CM Series	
Video Measuring Systems 10-1	11
Video Measuring Systems - iNEXIV VMA Series / NEXIV VMZ-S Series / NEXIV VMZ-H3030 Confocal Video Measuring Systems - NEXIV VMF-K Series	
Measuring Microscopes	2
Measuring Microscopes – MM-400N / MM-800N	
Profile Projectors / Data Processing Systems	13
Profile Projectors – V-12B / V-20B Data Processor – DP-E1A Data Processing Software – E-MAX	

DIGIMICRO - MF-1001 / MF-501 / MH-15M

Autocollimators / DIGIMICRO

Optical Flat / Optical Parallel / Standard 300 mm Scale

Autocollimators - 6B-LED / 6D-LED

Please refer to individual product brochures for further details.

14

15

Nikon's Industrial Microscopes utilize the CFI60-2 optical system, highly evaluated for providing a high NA combined with long WD.



Model offers various observation methods with reflected/transmitted illumination.

LV100NDA LED



LV150N LV150NA

Stand and illumination units are selectable according to observation methods and purpose of use.



Observation	
Method	

	BF	DF	DIC	FL	POL	2-Beam	Ph-C
EPI	V	V	V	V	V	V	_
DIA	V	V	V	_	V	_	V

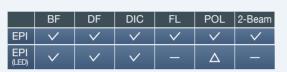
✓ : Available / — : Not available

Illuminator • Episcopic / Diascopic

Stage

- 3×2 Stage (stroke 75×50 mm)
- 6×4 Stage (stroke 150×100 mm)

*See the "LV-N Series" brochure for other compatible stages.



✓ : Available / — : Not available / Δ : Simple polarizing observation

- Episcopic
- 3×2 Stage (stroke 75×50 mm)
- 6×6 Stage (stroke 150×150 mm)
- *See the "LV-N Series" brochure for other compatible stages.

BF: Brightfield DF: Darkfield DIC: Differential Interference Contrast FL: Fluorescence POL: Polarizing 2-Beam: Two-Beam Interferometry Ph-C: Phase-Contrast

Upright Microscopes (Large-sized stage model)

L200N L200ND

Stage with stroke 200×200 mm is available. Suitable for ø200 mm wafer observation.



L300N L300ND

Stage with stroke 350×300 mm is available. Suitable for ø300 mm wafer observation.



Observation	
Method	

Illuminator

		BF	DF	DIC	S-POL	FL
n	EPI	V	V	V	~	V *
	DIA	*			_	_
	*L200N	D only		✓ : Avail	able / — : I	Not available

• L200N : Episcopic

L200ND : Episcopic / Diascopic

Stage • 8×8 Stage (stroke: 200×200 mm)

	BF	DF	DIC	S-POL	FL	
EPI	V	V	V	V	V	
DIA	✓ *			V		
*L300ND only						

- L300N : Episcopic
- L300ND: Episcopic / Diascopic
- 14×12 Stage (stroke: 350×300 mm)

BF: Brightfield DF: Darkfield DIC: Differential Interference Contrast S-POL: Simple Polarizing FL: Fluorescence

Inverted Metallurgical Microscopes

MA100N

MA100N is compact, inverted microscopes designed for brightfield and simple polarizing observations.



MA200

With its unique, solidbox structure, the MA200 offers high stability, durability, and a smaller footprint than conventional models.



	BF	DF	S-POL	DIC	FL				BF	DF	S-POL	DIC	FL
EPI	~	_	V	_		Ш		EPI	V	~	V	V	_
		*D					△: Only available with Halogen Lamp and Fi					amp and Fibe	er Illumination
Episcopic							Episcopic / Diascopic						
MA-SR-N Rectangular 3-plate Stage N (stroke 50×50 mm) MA-SP-N Plain Stage N TS2-S-SM Mechanical Stage CH (stroke 126×78 mm) Please use in combination with MA-SP-N Plain stage N.								• MA2-	-SR Mech	nanical St	age (strok	e 50×50 n	nm)
	EpisMA-STS2-S	Episcopic MA-SR-N Recta MA-SP-N Plair TS2-S-SM Mec	Episcopic MA-SR-N Rectangular 3-pla MA-SP-N Plain Stage N TS2-S-SM Mechanical Sta	EPI V - V: Avail *Dedicated refle • Episcopic • MA-SR-N Rectangular 3-plate Stage N (• MA-SP-N Plain Stage N • TS2-S-SM Mechanical Stage CH (strope	EPI	EPI V - V: Available / — : Not available *Dedicated reflected illumination models *Dedicated reflected reflected illumination models *Dedicated reflected refl	EPI		EPI	EPI ✓ — — EPI ✓ ✓: Available / — : Not available *Dedicated reflected illumination models. • Episcopic • Episcopic / Di • MA-SR-N Rectangular 3-plate Stage N (stroke 50×50 mm) • MA-SP-N Plain Stage N • TS2-S-SM Mechanical Stage CH (stroke 126×78 mm)	EPI ✓ — — EPI ✓ ✓	EPI ✓	EPI

BF: Brightfield DF: Darkfield DIC: Differential Interference Contrast S-POL: Simple Polarizing FL: Fluorescence

Polarizing Microscopes

LV100NPOL LED

Outstanding optical performance, perfect for a wide variety of imaging applications and polarizing techniques.



Ci POL

Compact polarizing microscope that balances optical performance and ease of use.



Observation Method	EPI DIA	BF ✓ ✓	POL V		EPI DIA	BF ✓	POL ✓	
Illuminator	• Episcop		: Available / — : Not available				: Available / — : Not available	
Stage		High precision rotating stage for polarizing observation			Rotating stage with stage clamp			

BF: Brightfield POL: Polarizing DF: Darkfield DIC: Differential Interference Contrast S-POL: Simple Polarizing FL: Fluorescence

Digital Sight Series

Microscope Camera

Digital Sight 1000

Equipped with a 2 megapixel CMOS image sensor, it can capture full HD microscope images. By connecting a microscope to this camera and HDMI monitor, movies and images can be captured and saved onto a pre-inserted SD card in the camera.



Max Frame Rate

Max Recordable Pixels



Digital Sight 100

Combined with industrial microscopes, the camera delivers 6.5-megapixel resolution (2944×2208 pixels). HDMI monitor output enables on-site observation without a PC.



Digital Sight 10

This high-resolution camera captures both color and monochromatic images at up to 6,000 x 3,984 pixels. This enables the wide range of images to be captured and then many of them to be stitched together making a single and large combined image.

55 fps (2000×1328)

6000×3984





30 fps (1920×1080) 60 fps (1600×900) 1920×1080 2944×2208

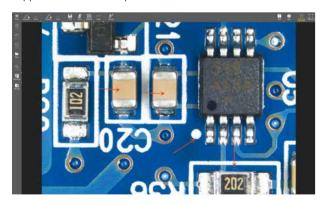
*Digital Sight 100, standalone, delivers up to 17.7-megapixel resolution (4864 x 3648 pixels).



NIS-Elements LE is a free software that allows intuitive control of microscope cameras from the PC. Supports Wi-Fi connectivity when used with the Digital Sight 100.

User Interface for naturally simple operation

Displays various menus for image capture, saving, display, measurement and annotations using intuitive icons. It also supports touch screen operation.



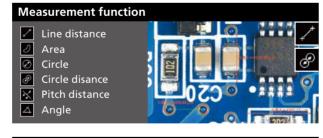
Scene mode

Ten camera setting patterns for optimal color reproduction and contrast for each microscope light source, observation method and type of sample, as well as custom settings, can be selected.

Industrial Scene Mode								
Wafer/IC Circuit board	MetalFlat Panel Display							

A wide variety of tools

Enables the conducting of simple measurements on images, with input of lines and comments. These can also be written onto and saved with the image, and measurement data can be output.





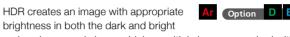
Graticule/scale function	
☐ Crosshairs ☐ Simple crosshairs ☐ Circle	



NIS-Elements D/Ar/Br/F offer image acquisition, analysis, visualization and data sharing tools. The software has a fully customizable user interface and can be seamlessly integrated with Nikon microscopes and cameras.

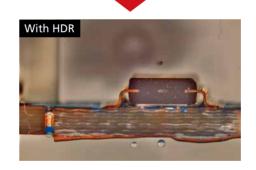
HDR (High Dynamic Range) **image acquisition**

brightness in both the dark and bright



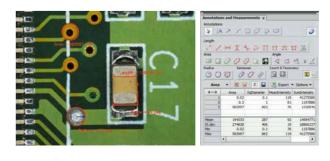
regions in a sample by combining multiple images acquired with different exposure settings. It is also possible to create HDR image using multiple captured images.





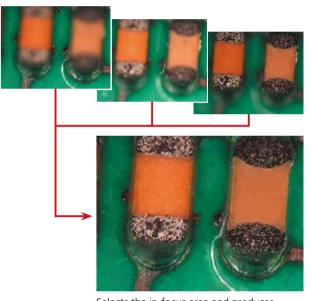
Manual measurement and image annotation

Manual measurement allows easy measurement of length and area by drawing lines or an object directly on the image. The results can be attached to the image, and also exported as text or to an Excel spreadsheet.



EDF (Extended Depth of Focus)

Creates a single, all-in-focus image from images of differing focus. Such images can now be created by simply turning the focus knob.



Selects the in-focus area and produces one all-in-focus image

Auto measurement (Object Counting)

Ar Br Option D Performs binarization on images using previously set thresholds to measure the number, area, brightness, etc. of identified objects.



Objective Lenses

CFI60-2 / CFI60

Nikon's CFI₆₀-2/CFI₆₀ optical systems are highly evaluated for their unique concept of high NA combined with a long working distance. These lenses have been developed further and evolved achieving the apex in long working distance specifications, correct chromatic aberration, and an optimized lens weight.









NA: Numerical Aperture BF: Brightfield DF: Darkfield POL: Polarizing S-POL: Simple Polarizing DIC: Differential Interference Contrast UV-FL: UV Fluorescence FL: EPI Fluorescence

	Model	Magnification	NA	WD (mm)	BF	DF	POL	S-POL	DIC	UV-FL	FL
	T Plan EPI	1×	0.03	3.8	~	_	_	_	_	<u> </u>	_
	Plan (Achromat)	2.5×	0.075	6.5	~		_		_	_	_
	TU Plan Fluor EPI	5×	0.15	23.5	~	_	_	~	∨A	~	~
	Universal Plan Fluor (Semi-apochromat)	10×	0.3	17.5	~	_	_	~	∨A	~	~
		20×	0.45	4.5	~			~	∨A	~	~
		50×	0.8	1.0	~			~	∨A	~	~
		100×	0.9	1.0	~	_	_	~	∨A	~	~
	TU Plan Apo EPI	50×	0.8	2.0	~	_	_	~	∨ A	_	~
	Universal Plan Apo (Apochromat)	100×	0.9	2.0	~	_	_	~	∨A	_	~
		150×	0.9	1.5	~			~	∨A		~
	TU Plan Fluor EPI P	5×	0.15	23.5	~	_	V	~	∨ A	~	~
	Polarizing Universal Plan Fluor (Semi-apochromat)	10×	0.3	17.5	~		~	~	∨A	V	~
		20×	0.45	4.5	~	_	~	~	∨A	~	~
		50×	0.8	1.0	V	_	~	~	✓ A	V	~
CEL 3		100×	0.9	1.0	~	_	V	~	∨ A	V	~
CFI60-2	TU Plan EPI ELWD	20×	0.4	19.0	~	_	_	~	∨B	_	~
	Long Working Distance Universal Plan (Semi-apochromat)	50×	0.6	11.0	~			~	∨B	_	~
	(зепп-ароспютах)	100×	0.8	4.5	~	_	_	~	∨B	_	~
	T Plan EPI SLWD	10×	0.2	37.0	~				_	_	~
	Super Long Working Distance Plan (Semi-apochromat)	20×	0.3	30.0	\ \		_	_	_	_	~
	(Semi-apochromat)	50×	0.4	22.0	~	_	_		_	_	~
		100×	0.6	10.0	~		_		_	_	~
	TU Plan Fluor BD	5×	0.15	18.0	V	~	_	~	∨A	V	~
	Universal Plan Fluor (Semi-apochromat)	10×	0.3	15.0	~	~	_	~	∨A	~	~
		20×	0.45	4.5	~	~	_	~	∨A	~	~
		50×	0.8	1.0	~	~			∨A	~	~
		100×	0.9	1.0	~	~	_	~	∨A	~	~
	TU Plan Apo BD	50×	0.8	2.0		~			∨A		~
	Universal Plan Apo (Apochromat)	100×	0.9	2.0	~	~	_		∨A	_	~
		150×	0.9	1.5		~	_	~	∨A	_	~
	TU Plan BD ELWD	20×	0.4	19.0	~	~	_	~	∨B	_	~
	Long Working Distance Universal plan (Semi-apochromat)	50×	0.6	11.0	V	V	_	~	∨B	_	~
		100×	0.8	4.5	~	~	_	~	∨B	-	~
	L Plan EPI (Achromat)	40×	0.65	1.0	~	_	_	_	_	_	~
	L Plan EPI CR	20×	0.45	10.9–10.0	~	_		_	_	_	~
	LCD Substrate Inspection Plan (Achromat)	50×	0.7	3.9–3.0	~		_		_	_	~
	*Offers valid while supplies last	100×	0.85	1.2-0.85	V	_			_	_	~
CFI60		100×	0.85	1.3-0.95	~	_	_	_	_	-	~
CI 160	LE Plan EPI (Achromat)	5×	0.1	31	~	_				_	~
		10×	0.25	13	V	_	_	_	_	_	~
		20×	0.4	3.6	~	_			_	_	~
		50×	0.75	0.5	~	_	_		_	_	~
		100×	0.9	0.31	~	_	_	_	_	_	~

✓ : Available / — : Not available *A: Set prism position at A / B: Set prism position at B

For Incorporation into Microscopes

Modular Focusing Units

IM-4, LV-IM/LV-IMA, LV-FM/LV-FMA

Suitable for incorporating into systems, these focusing units enable the mounting of a universal illuminator and a motorized nosepiece.

	IM-4	LV-IM/LV-IMA	LV-FM/LV-FMA
Туре	Manual	Manual / Motorized	Manual / Motorized
Vertical stroke	30 mm	30/20 mm	30/20 mm



Compact Reflected Microscopes

CM Series

Ultra-compact reflected microscopes designed for integration into production lines to observe on monitors.



	CM-10A/CM-10L	CM-20A/CM-20L	CM-30A2/CM-30L2	CM-70L	CM-5A				
Camera mount			C-mount						
Tube lens magnification	1×	0.5×	1×	0.4×/1×	_				
Tube lens focal distance	200 mm	100 mm	200 mm	80/200 mm	—				
Magnification on CCD surface		11 mm							
Compatible objectives		A series: CF IC El L series: CFl60-2 / CFl	PI Plan objectives 60 EPI Plan objectives		Objectives for Nikon MM series				
Illumination optical system		Koehler illuminat	tion (high-quality telecer	ntric illumination)					
Attached surfaces	3	3	4	3	3				
Dimensions (W×D×H)	40×40×224.5 mm	40×40×125.5 mm	40×40×107.3 mm	40×117×156.1 mm	40×40×186.5 mm				
Weight (approx)	440 g	290 g	400 g	690 g	410 g				

Wafer Loaders

Nikon's proprietary technology ensures reliable loading of ultra-thin 100 μ m wafers. The NWL 200 series achieve highly reliable loading, suitable for inspection of next-generation semiconductors.

	Diameter	ø200 mm / ø150 mm
Wafer	Minimum thickness (standard)	300 um
	Minimum thickness (option)	100 um
Surface	, back side macro inspection	✓

*Optional special wafer loader is also available. Please ask Nikon for detail.

NWL200 Series



Please refer to individual product brochures for further details.

Wide variety of stage strokes and magnifications are available for various customer requirements.

Standard Model

NEXIV VMZ-S3020

Main Body (Type / Stage Stroke)

VMA

Model VMA-2520 VMA-4540 VMA-6555

Wide FOV Model

Applications Electronic parts, resin molding parts, various mold parts, press parts, die cast parts, etc.



VM7-S Model VMZ-S3020/VMZ-S4540/VMZ-S6555 Applications Semiconductor packages, high density PCB's, lead frames, MEMS, connectors, precision mechanical parts, etc.

High-precision Model VM7-H Model VMZ-H3030 Applications Micro boards (line width, height), next-generation semiconductor packages (WLP, bump height), precision molds, rewiring masks, MEMS masks, etc. NEXIV VMZ-S4540

Model		Wide FOV				High-precision	
XY Stroke	250×200 mm	450×400 mm	650×550 mm	300×200 mm	450×400 mm	650×550 mm	300×300 mm
Wide FOV Head	✓	~	✓	✓	✓	✓	
Standard Head				~	~	✓	✓
High-Magnification Head				~	~	✓	~
Z-axis Stroke	200 mm	200 mm	200 mm	200 mm	200 mm	200 mm	150 mm
Max. guaranteed loading capacity	15 kg	20 kg	30 kg	20 kg	40 kg	50 kg	30 kg
Maximum permissible error (Eux, Mpe Euy, Mpe)	2+8 <i>L</i> /1000 μm	2+6 <i>L</i> /10	000 µm		0.6+2 <i>L</i> /1000 μm		
Maximum permissible error (E∪z, MPE)	3+L/50 µm	3+ <i>L</i> /10	00 μm		0.9+ <i>L</i> /150 µm		

L = Length in mm

Zoom Heads

Type A

Wide FOV and long working distance enables

comfortable operation. Laser AF and Touch Probe can be attached as optional

accessories.

*Touch Probe is an option only for VMA series.

Type 1–4

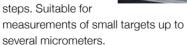
Equipped with top, bottom,

and oblique

ring lights with adjustable angles. TTL (Through the Lens) Laser AF is a standard tool that can scan surfaces at 1000 points/second.

Type TZ

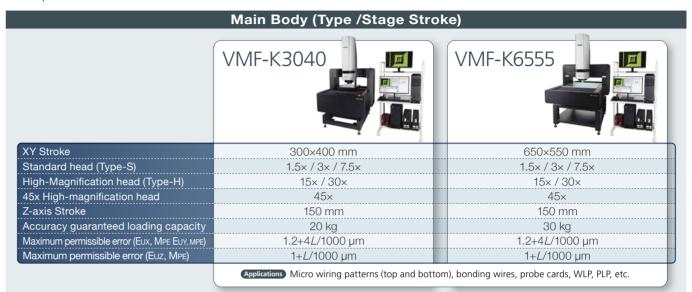
Equipped with 1-120x ultra high zoom ratio with 8 steps. Suitable for



NEXIV VMZ-H3030

FOV	W(mm)× D(mm)	13.3 10.0	9.33 7.01	7.8 5.8	4.7 3.5	2.6 1.9	2.33 1.75	1.33 1.00	1.165 0.875	0.622 0.467									WD
Wide FOV Head	Type A	•		-	-	-		-											73.5 mm
Standard Head	Type 1		•		-		-		-	-									
	Type 2				•		-		•		-	_							50 mm
	Туре 3						•		-		-		-	_					
High- Magnification Head	Type 4								•		-		-		-	—			30 mm
	Type TZ				•		-		•	-			_		-		-	-	9.8 mm

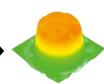
Equipped with brightfield and confocal optics, Confocal NEXIV series are capable of high-speed, high-resolution inspection of fine 3D shapes.



							oom										
FOV*	W(mm)× D(mm)	7.81 5.85	3.91 2.93	1.95 1.47	1.56 1.17	1.27 0.95	0.98 0.73	0.78 0.59	0.63 0.47	0.52 0.39	0.39 0.29	0.26 0.19	0.20 0.15	0.10 0.078	0.099 0.074	0.049 0.037	WD
Standard head (Type-S)	1.5×	•	-	-			->-			-							24 mr
	3×		9	-			-			-		-					24 mr
	7.5×				•			-			-		->-	—			5 mi
High-magnification	15×					•		-			-		-		_		20 mi
head (Type-H)	30×								•		-9		-9-		-	—	5 mr
45x High-magnific	ation head								•		-	3	-		-	_	5 mr
	onfocal/Brig	ghtfield	Co	nfocal	*The	FOV of t	he brigh	nt field c	ptics are	e indicat	ed.						

The NEXIV VMF-K series can perform full-field height measurement using confocal optics as well as 2D measurement with brightfield images. Special samples that are difficult to detect with brightfield can be clearly calculated with confocal measurement.





Brightfield image

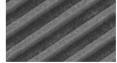
Image with height information

Bird's-eye view

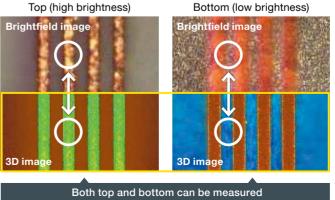
High contrast sample (copper wire on print board etc.)

Confocal observation accurately captures the shape, even for samples that are difficult to measure accurately in brightfield, due to effects such as halation.

Please refer to individual product brochures for further details.

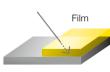


Actual shape (SEM image)



Highly transparent and thin samples (metal surface films, semiconductor resists, etc.)

For transparent samples with unstable light reflection, confocal observation can accurately detect two points: the transparent surface and the metal surface.



Metal surface



Unstable reflection makes it difficult to detect the

Confocal

Both the top and bottom heights can be detected accurately.

Measuring Microscopes

Focused on high-precision and easy operability, a wide range of MM-products are available.



Large-Stage Model
MM-800N

	50×50 mm / 5 kg	✓	V				
	100×100 mm / 15 kg	✓					
Stage Size/ Loading	150×100 mm / 15 kg	✓	✓				
Capacity	200×150 mm / 20 kg	_	✓				
	250×150 mm / 20 kg	_	✓				
	300×200 mm / 20 kg	_	✓				
Max. Sample H	leight	150 mm	200 mm				
Optical Head	Monocular	✓	_				
	Binocular	✓	✓				
X-Y-Z	2-axis	✓	✓				
X 1 Z	3-axis	✓	✓				
CCD		✓	✓				
Obj. Magnificat	tion	1×/3×/5×/10×/2	1×/3×/5×/10×/20×/50×/100×				

✓ : Available / — : Not available

ММ Туре

With Nikon's optical technology and highly precise stages, high-precision measurement can be achieved.



Universal Type

Offers a line-up compatible with dimensional measurement and various observation methods.



High-Precision Stages

The coarse/fine changeover lever and the RESET and SEND buttons are located near the X- and Y-axis knobs.







Y-axis Knob

Focusing Aid (FA)

Front Focus

The Split-Prism FA delivers sharp patterns to allow accurate focusing during Z-axis measurements.

FA patterns are clearly visible because they are split vertically.







Focused Rear Focus

Profile Projectors

Nikon's profile projectors apply the principles of optics to the inspection of manufactured parts by projecting magnified silhouettes on a screen.

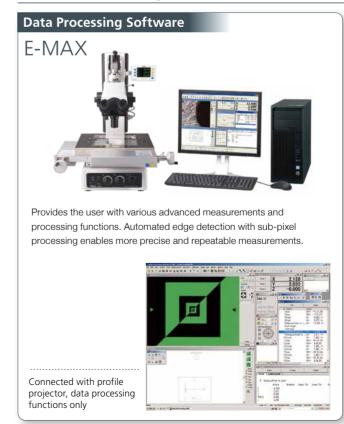


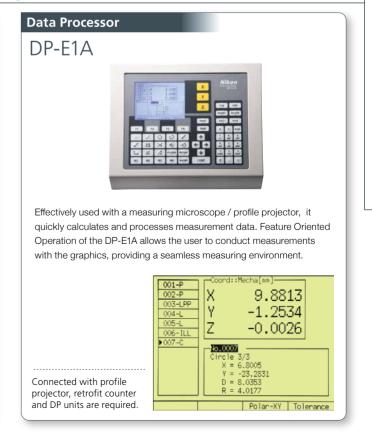


	50×50 mm / 5 kg	\checkmark	✓				
	100×100 mm / 15 kg	✓	✓				
Stage Size/ Loading Capacity	150×100 mm / 15 kg	✓	✓				
	200×150 mm /20 kg	√	✓				
	250×150 mm /20 kg	✓	✓				
Max. Sample	e Height	100 mm*²	150 mm				
Screen		305 mm	500 mm				
Image		Erect	Inverted				
Projection	Magnification	5×/10×/20×/25×/50×/100×/200×	5×/10×/20×/50×/100×				
Lens	FOV (with 10× lens)*1	30.5 mm	50 mm				
Digital Protra	actor	√	\checkmark				
Digital Coun	ter	✓	✓				

^{*1:} Actual FOV = Effective diameter of screen / Lens magnification *2: Maximum sample height is 70 mm when 200×150 mm stage is installed.

Data Processing Systems for Measuring Microscopes and Profile Projectors





^{√ :} Available / — : Not available

Autocollimators

Autocollimator is an easy-to-use but precise metrology instrument for angularity, parallelism, perpendicularity, straightness of precision components machine guide-way and many other applications.



Observation method	6B-LED: Brightfield, 6D-LED: Darkfield					
Readout system	Adjustment in viewfield and reading on micrometer					
Measuring range	30 minutes of arc (both vertical and horizontal axes)					
Minimum range 0.5 seconds of arc						

DIGIMICRO

With built-in photoelectric digital length measuring systems, DIGIMICRO offers flawless contact measurements of dimension, thickness, and depth.

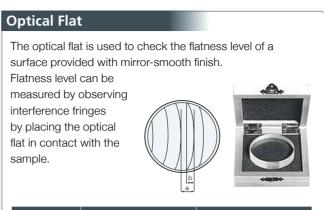






Main unit	MF-1001	MF-501	MH-15M
Measuring range	0–100 mm	0–50 mm	0–15 mm
Accuracy (20°C)	3 µm	1 µm	0.7 μm
Measuring force	Downward 1.13 to 1.62N (variable to about 0.29N) Lateral 0.64 to 1.23N	Downward 1.23 to 1.81N (variable to about 0.44N) Lateral 0.64 to 1.23N	Upward 0.25N Downward 0.64N Lateral 0.44N (lifting release included)
Operating temperature	0 to +40°C		

Optical Flat / Optical Parallel / Standard 300 mm Scale



Diameter	Glass (ø60 mm)	Glass (ø130 mm)
Thickness	15 mm	27 mm
Flatness	0.1 µm	0.1 µm

Standard 300mm Scale

Gauges stage travel accuracy up to 300 mm. Both 10 mm-interval sensor patterns and calibrations are provided.

Made of the glass with low coefficient of thermal expansion, for minimizing thermal influence.

*Within 1 µm against compensation values.

Optical Parallel

Both planes of the optical parallel have been precisely finished flat and parallel.

It is used to check the flatness and parallel levels of a sample

by observing interference fringes by placing the optical parallel in contact with the sample.

Diameter	30 mm	
Thickness	12 mm / 12.12 mm / 12.25 mm / 12.37 mm	
Flatness	within 0.1 µm	
Parallelism	within 0.2 μm	

^{*}Optical flats and parallels with greater precision are available by custom orders.

15

Please refer to individual product brochures for further details.

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TO ENSURE CORRECT USAGE, READ THE CORRESPONDING MANUALS CAREFULLY BEFORE USING THE EQUIPMENT.



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